Correction to: Facile morphology control of high aspect ratio patterned Si nanowires by metal-assisted chemical etching

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The original version of this article unfortunately contained an error in one of the co-author's name. Part of family name was erroneously tagged as given name. The correct name should be "Mostafa Afifi Hassan".

The original article has been corrected.

The original article can be found online at <https://doi.org/10.1007/s10854-018-9929-8>.

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